

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant: Horning et al.

Attorney Docket No. H16-16009  
HOOO-1-1200

Serial No.: 09/873,931

Group Art Unit: 2814

Filing Date: June 4, 2001

Examiner: RAO, Shrinivas

Title: APPLICATIONS OF A STRAIN-COMPENSATED HEAVILY DOPED ETCH  
STOP FOR SILICON STRUCTURE FORMATION

**RESPONSE TO FINAL OFFICE ACTION**

**TO THE COMMISSIONER OF PATENTS:**

**AMENDMENT AND RESPONSE**

*Enter RCE  
file on 10/20/05  
T. Steptoe*